······································	Application No.	Applicant(s)	
	10/774,558 DIADDARIO, LEONARD L.		JNIADD I
Notice of Allowability	Examiner	Art Unit	JNARD L.
•	Edna Wong	1753	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	ears on the cover sheet wi (OR REMAINS) CLOSED in) or other appropriate committed	ith the correspondence ad n this application. If not including unication will be mailed in du	uded ue course. THIS
1. \boxtimes This communication is responsive to <u>Amendment dated Ju</u>	<u>une 21, 2007</u> .		
2. The allowed claim(s) is/are 2-20 and 22.			
3. ☐ Acknowledgment is made of a claim for foreign priority unallocation of the: a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have	e been received. e been received in Application	on No	cation from the
International Bureau (PCT Rule 17.2(a)). * Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 4. A SUBSTITUTE OATH OR DECLARATION must be subminformal patent application (PTO-152) which give	MENT of this application. nitted. Note the attached EX.	AMINER'S AMENDMENT o	·
5. CORRECTED DRAWINGS (as "replacement sheets") must	st he submitted		
(a) ☐ including changes required by the Notice of Draftspers		w (PTO-948) attached	
1) hereto or 2) to Paper No./Mail Date	-		
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1	's Amendment / Comment on tale.	he drawings in the front (not	the back) of
each sheet. Replacement sheet(s) should be labeled as such in a 6. DEPOSIT OF and/or INFORMATION about the depo	_		Note the
attached Examiner's comment regarding REQUIREMENT			
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 🗀 Notice of In	eformal Datast Application	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	<u> </u>	nformal Patent Application	
Information Disclosure Statements (PTO/SB/08),	Paper No.	summary (PTO-413), /Mail Date : Amendment/Comment	
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit		Statement of Reasons for A	Allowance
of Biological Material	9. ☐ Other)ung

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

Claims 2-3, 11, 18-20 and 22 are allowable over the prior art of record because the prior art does not teach or suggest a process for the electrodeposition of a nickel or nickel-alloy coating on a substrate, the process comprising the steps of immersing and electrodepositing as presently claimed, esp., wherein the bath comprises an additive having the general formula:

$$[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$$

wherein R₁, R₂ and R₃ are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and Xⁿ⁻ is an n-valent inorganic or organic anion and n equals 1 or 2.

Claims 4, 10 and 12-17 are allowable over the prior art of record because the prior art does not teach or suggest an aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising: (a) nickel ions and (b) an additive having the general formula:

$$[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$$

wherein R₁, R₂ and R₃ are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and Xⁿ⁻ is an n-valent inorganic or organic anion and n equals 1 or 2.

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Claim **5** is allowable over the prior art of record because the prior art does not teach or suggest an aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising: (a) nickel ions, (b) at least one Class I brightener, and (c) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-} is an n-valent inorganic or organic anion and n equals 1 or 2.

Claim 6 is allowable over the prior art of record because the prior art does not teach or suggest an aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising: (a) nickel ions, (b) at least one Class II brightener, and (c) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or
$$[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-} is an n-valent inorganic or organic anion and n equals 1 or 2.

Claim 7 is allowable over the prior art of record because the prior art does not teach or suggest an aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising: (a) nickel ions, (b) at least one Class I

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brightener, (c) at least one Class II brightener, and (d) an additive having the general formula:

$$[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$$

wherein R₁, R₂ and R₃ are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and Xⁿ⁻ is an n-valent inorganic or organic anion and n equals 1 or 2.

Claims 8 and 9 are allowable over the prior art of record because the prior art does not teach or suggest an aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising: (a) nickel ions, (b) alloying metal ions, (c) at least one Class I brightener, (d) at least one Class II brightener, and (e) an additive having the general formula:

$$[H_2C = CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-}$$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-} is an n-valent inorganic or organic anion.

The prior art does not contain any language that teaches or suggests the above.

Ostrow teaches diallyl propargyl amine and triallyl propargyl amine. Therefore, a person skilled in the art would not have been motivated to adopt the above conditions, and a prima facie case of obviousness cannot be established.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Edna Wong whose telephone number is (571) 272-1349. The examiner can normally be reached on Mon-Fri 7:30 am to 4:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam Nguyen can be reached on (571) 272-1342. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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Edna Wong Primary Examiner Art Unit 1753

EW July 2, 2007